

ABSTRACT OF THE DISCLOSURE

A mask structure comprises a transparent substrate, a cover layer formed on the transparent substrate, and a transparent conductive thin film, with which the cover layer and the transparent substrate is covered, wherein the cover layer is provided with exposure patterns. Moreover, a process of fabricating a mask comprising the steps of forming a cover layer provided with exposure patterns on a transparent substrate and then covering the transparent substrate and the cover layer uniformly with a transparent conductive thin film.